Ser. No. 09/429,719

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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12/B
W.M.
9/20/01

APPLICANT(S):	Aratani et al.	OLD DOCKET NO.:	P99,2247
		NEW DOCKET NO.:	9792486-0100
SERIAL NO.:	09/429,719	GROUP ART UNIT:	1753
DATE FILED:	October 29, 1999	EXAMINER:	R. McDonald

INVENTION: "THIN FILM FORMATION USE SPUTTERING TARGET MATERIAL, THIN FILM FORMED USING SAME, AND OPTICAL RECORDING MEDIUM"

Entered
10/9/01
W.M.
R.C.E.
Request

AMENDMENT "C" AFTER FINAL

Hon. Assistant Commissioner for Patents
BOX AF
Washington, DC 20231

S I R:

This amendment is filed in response to the Office Action of May 17, 2001. Please reconsider the application in view of the amendment and remarks presented below.

IN THE CLAIMS

Please amend claims 1, 7, 15, and 16 as follows:

B1

1. (Twice Amended) A method of forming a thin film comprising the step of: forming an AgPd alloy thin film using a sputtering target material, the AgPd alloy thin film comprising Pd in an amount ranging from 0.5 to 4.9 atomic % and Cu in an amount ranging from 0.1 to 3.5 atomic %.

B2

7. (Twice Amended) A method of forming a thin film comprising the step of: forming an AgPdTi alloy thin film using a sputtering target material, the AgPdTi alloy comprising Pd in an amount ranging from 0.1 to 1.5 atomic %, Ti in an amount ranging from 0.1 to 2.9 atomic %, and Cu in an amount ranging from 0.1 to 3.5 atomic %.

B3

15. (Amended Claim 13) The method of claim 1, wherein the thin film has a thickness from approximately 500 Angstroms to approximately 1500 Angstroms.